

L Number	Hits	Search Text	DB	Time stamp
1	7136	(SEM or (scanning adj electron adj microscop\$3)) and electron and (resist or photoresist)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/11/18 18:54
2	3883	((SEM or (scanning adj electron adj microscop\$3)) and electron and (resist or photoresist)) and imag\$5	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/11/18 19:24
3	626	((SEM or (scanning adj electron adj microscop\$3)) and electron and (resist or photoresist)) and imag\$5) and ((critical\$4 or characteristic) near2 dimension\$4)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/11/18 19:25
4	70	((SEM or (scanning adj electron adj microscop\$3)) and electron and (resist or photoresist)) and imag\$5) and ((critical\$4 or characteristic) near2 dimension\$4) and ((edge or pattern) near width)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/11/18 19:25
5	7	((SEM or (scanning adj electron adj microscop\$3)) and electron and (resist or photoresist)) and imag\$5) and ((critical\$4 or characteristic) near2 dimension\$4) and ((edge or pattern) near width) and (edge near2 bias\$4)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/11/18 18:56
6	7	((SEM or (scanning adj electron adj microscop\$3)) and electron and (resist or photoresist)) and imag\$5) and ((critical\$4 or characteristic) near2 dimension\$4) and ((edge or pattern) near width) and (edge near2 bias\$4) and focus\$4	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/11/18 18:57
7	7	((SEM or (scanning adj electron adj microscop\$3)) and electron and (resist or photoresist)) and imag\$5) and ((critical\$4 or characteristic) near2 dimension\$4) and ((edge or pattern) near width) and (edge near2 bias\$4) and focus\$4) and patterns	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/11/18 18:57
9	4	((SEM or (scanning adj electron adj microscop\$3)) and electron and (resist or photoresist)) and imag\$5) and ((critical\$4 or characteristic) near2 dimension\$4) and ((edge or pattern) near width) and (edge near2 bias\$4) and focus\$4) and patterns) and ((calculat\$5 or determin\$5 or measur\$6) with (chang\$4 or bias\$4)) and (correct\$4 with (dos\$4 or exposure))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/11/18 19:07
10	2	((SEM or (scanning adj electron adj microscop\$3)) and electron and (resist or photoresist)) and imag\$5) and ((critical\$4 or characteristic) near2 dimension\$4) and ((edge or pattern) near width) and (edge near2 bias\$4) and focus\$4) and patterns) and ((calculat\$5 or determin\$5 or measur\$6) with (chang\$4 or bias\$4)) and model\$4	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/11/18 19:01
12	4	((SEM or (scanning adj electron adj microscop\$3)) and electron and (resist or photoresist)) and imag\$5) and ((critical\$4 or characteristic) near2 dimension\$4) and ((edge or pattern) near width) and (edge near2 bias\$4) and focus\$4) and patterns) and ((calculat\$5 or determin\$5 or measur\$6) with (chang\$4 or bias\$4)) and reference) and (correct\$4 with (dos\$4 or exposure))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/11/18 19:02

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13	4	(((((SEM or (scanning adj electron adj microscop\$3)) and electron and (resist or photoresist)) and imag\$5) and ((critical\$4 or characteristic) near2 dimension\$4)) and ((edge or pattern) near width)) and (edge near2 bias\$4)) and focus\$4) and patterns) and ((calculat\$5 or determin\$5 or measur\$6) with (chang\$4 or bias\$4))) and ((correct\$4 or compensat\$5) with (dos\$4 or exposure))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/11/18 19:07
8	7	(((((SEM or (scanning adj electron adj microscop\$3)) and electron and (resist or photoresist)) and imag\$5) and ((critical\$4 or characteristic) near2 dimension\$4)) and ((edge or pattern) near width)) and (edge near2 bias\$4)) and focus\$4) and patterns) and ((calculat\$5 or determin\$5 or measur\$6) with (chang\$4 or bias\$4)))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/11/18 19:08
11	7	(((((SEM or (scanning adj electron adj microscop\$3)) and electron and (resist or photoresist)) and imag\$5) and ((critical\$4 or characteristic) near2 dimension\$4)) and ((edge or pattern) near width)) and (edge near2 bias\$4)) and focus\$4) and patterns) and ((calculat\$5 or determin\$5 or measur\$6) with (chang\$4 or bias\$4))) and reference	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/11/18 19:08
14	1545	((SEM or (scanning adj electron adj microscop\$3)) and electron and (resist or photoresist)) and imag\$5) and (electron with imag\$5)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/11/18 19:24
15	278	((SEM or (scanning adj electron adj microscop\$3)) and electron and (resist or photoresist)) and imag\$5) and (electron with imag\$5)) and ((critical\$4 or characteristic) near2 dimension\$4)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/11/18 19:25
16	36	((SEM or (scanning adj electron adj microscop\$3)) and electron and (resist or photoresist)) and imag\$5) and (electron with imag\$5)) and ((critical\$4 or characteristic) near2 dimension\$4)) and ((edge or pattern) near width)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/11/18 19:27
17	33	((SEM or (scanning adj electron adj microscop\$3)) and electron and (resist or photoresist)) and imag\$5) and (electron with imag\$5)) and ((critical\$4 or characteristic) near2 dimension\$4)) and ((edge or pattern) near width)) and monitor\$4	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/11/18 19:27

L Number	Hits	Search Text	DB	Time stamp
18	12771	(SEM or (scanning adj electron adj microscop\$4)) and monitor\$4	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/11/18 19:29
19	1407	((SEM or (scanning adj electron adj microscop\$4)) and monitor\$4) and (electron near5 imag\$5)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/11/18 19:29
20	171	((SEM or (scanning adj electron adj microscop\$4)) and monitor\$4) and (electron near5 imag\$5) and ((critical\$4 or characteristic\$4) near2 dimension\$4)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/11/18 19:30
21	158	((SEM or (scanning adj electron adj microscop\$4)) and monitor\$4) and (electron near5 imag\$5) and ((critical\$4 or characteristic\$4) near2 dimension\$4) and pattern	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/11/18 19:30
22	21	((SEM or (scanning adj electron adj microscop\$4)) and monitor\$4) and (electron near5 imag\$5) and ((critical\$4 or characteristic\$4) near2 dimension\$4) and pattern) and (edge near2 width)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/11/18 19:31
23	14	((SEM or (scanning adj electron adj microscop\$4)) and monitor\$4) and (electron near5 imag\$5) and ((critical\$4 or characteristic\$4) near2 dimension\$4) and pattern) and (edge near2 width) and ((calculat\$5 or determin\$4) near6 (critical\$4 or characteristic\$4))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/11/18 19:33
24	9	((SEM or (scanning adj electron adj microscop\$4)) and monitor\$4) and (electron near5 imag\$5) and ((critical\$4 or characteristic\$4) near2 dimension\$4) and pattern) and (edge near2 width) and ((calculat\$5 or determin\$4) near6 (critical\$4 or characteristic\$4)) and ((calculat\$4 or determin\$4) near5 (exposure or dos\$4))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/11/18 19:34
26	5	((SEM or (scanning adj electron adj microscop\$4)) and monitor\$4) and (electron near5 imag\$5) and ((critical\$4 or characteristic\$4) near2 dimension\$4) and pattern) and (edge near2 width) and ((calculat\$5 or determin\$4) near6 (critical\$4 or characteristic\$4)) and ((calculat\$4 or determin\$4) near5 (exposure or dos\$4)) and (((SEM or (scanning adj electron adj microscop\$4)) and monitor\$4) and (electron near5 imag\$5) and ((critical\$4 or characteristic\$4) near2 dimension\$4) and pattern) and (edge near2 width) and ((calculat\$5 or determin\$4) near6 (critical\$4 or characteristic\$4)) and model\$4)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/11/18 19:35

27	5	(((((SEM or (scanning adj electron adj microscop\$4)) and monitor\$4) and (electron near5 imag\$5)) and ((critical\$4 or characteristic\$4) near2 dimension\$4)) and pattern) and (edge near2 width)) and ((calculat\$5 or determin\$4) near6 (critical\$4 or characteristic))) and ((calculat\$4 or determin\$4) near5 (exposure or dos\$4))) and (((SEM or (scanning adj electron adj microscop\$4)) and monitor\$4) and (electron near5 imag\$5)) and ((critical\$4 or characteristic\$4) near2 dimension\$4)) and pattern) and (edge near2 width)) and ((calculat\$5 or determin\$4) near6 (critical\$4 or characteristic))) and model\$4)) and correct\$5	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/11/18 19:50
28	5	(((((SEM or (scanning adj electron adj microscop\$4)) and monitor\$4) and (electron near5 imag\$5)) and ((critical\$4 or characteristic\$4) near2 dimension\$4)) and pattern) and (edge near2 width)) and ((calculat\$5 or determin\$4) near6 (critical\$4 or characteristic))) and ((calculat\$4 or determin\$4) near5 (exposure or dos\$4))) and (((SEM or (scanning adj electron adj microscop\$4)) and monitor\$4) and (electron near5 imag\$5)) and ((critical\$4 or characteristic\$4) near2 dimension\$4)) and pattern) and (edge near2 width)) and ((calculat\$5 or determin\$4) near6 (critical\$4 or characteristic))) and model\$4)) and correct\$5	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/11/18 19:51
25	10	(((((SEM or (scanning adj electron adj microscop\$4)) and monitor\$4) and (electron near5 imag\$5)) and ((critical\$4 or characteristic\$4) near2 dimension\$4)) and pattern) and (edge near2 width)) and ((calculat\$5 or determin\$4) near6 (critical\$4 or characteristic))) and model\$4)) and correct\$5) and width	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/11/18 19:50
29	5	(((((SEM or (scanning adj electron adj microscop\$4)) and monitor\$4) and (electron near5 imag\$5)) and ((critical\$4 or characteristic\$4) near2 dimension\$4)) and pattern) and (edge near2 width)) and ((calculat\$5 or determin\$4) near6 (critical\$4 or characteristic))) and ((calculat\$4 or determin\$4) near5 (exposure or dos\$4))) and model\$4	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/11/18 19:49
30	10	(((((SEM or (scanning adj electron adj microscop\$4)) and monitor\$4) and (electron near5 imag\$5)) and ((critical\$4 or characteristic\$4) near2 dimension\$4)) and pattern) and (edge near2 width)) and ((calculat\$5 or determin\$4) near6 (critical\$4 or characteristic))) and model\$4) and correct\$5	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/11/18 19:50
31	10	(((((SEM or (scanning adj electron adj microscop\$4)) and monitor\$4) and (electron near5 imag\$5)) and ((critical\$4 or characteristic\$4) near2 dimension\$4)) and pattern) and (edge near2 width)) and ((calculat\$5 or determin\$4) near6 (critical\$4 or characteristic))) and model\$4) and correct\$5) and width	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/11/18 19:53

L Number	Hits	Search Text	DB	Time stamp
41	15192	(electron adj beam) and lithograph\$3	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/11/18 21:05
42	79	((electron adj beam) and lithograph\$3) and (edge near width)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/11/18 21:11
43	27	((electron adj beam) and lithograph\$3) and (edge near width)) and ((calculat\$5 or determin\$4) with (dimension\$4))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/11/18 21:11
44	16	((electron adj beam) and lithograph\$3) and (edge near width)) and ((calculat\$5 or determin\$4) with (dimension\$4))) and ((second or test or reference) near (pattern or portion))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/11/18 21:11
45	12	((electron adj beam) and lithograph\$3) and (edge near width)) and ((calculat\$5 or determin\$4) with (dimension\$4))) and ((second or test or reference) near (pattern or portion))) and ((calculat\$5 or determin\$4) with (bias\$4 or deviat\$4))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/11/18 21:12
46	11	((electron adj beam) and lithograph\$3) and (edge near width)) and ((calculat\$5 or determin\$4) with (dimension\$4))) and ((second or test or reference) near (pattern or portion))) and ((calculat\$5 or determin\$4) with (bias\$4 or deviat\$4))) and focus\$4	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/11/18 21:12
47	3	((electron adj beam) and lithograph\$3) and (edge near width)) and ((calculat\$5 or determin\$4) with (dimension\$4))) and ((second or test or reference) near (pattern or portion))) and ((calculat\$5 or determin\$4) with (bias\$4 or deviat\$4))) and focus\$4) and (exposure near2 energ\$4)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/11/18 21:12
48	168	((electron adj beam) and lithograph\$3) and (edge near2 width)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/11/18 21:11
49	55	((electron adj beam) and lithograph\$3) and (edge near2 width)) and ((calculat\$5 or determin\$4) with (dimension\$4))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/11/18 21:11
50	31	((electron adj beam) and lithograph\$3) and (edge near2 width)) and ((calculat\$5 or determin\$4) with (dimension\$4))) and ((second or test or reference) near (pattern or portion))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/11/18 21:17
51	16	((electron adj beam) and lithograph\$3) and (edge near2 width)) and ((calculat\$5 or determin\$4) with (dimension\$4))) and ((second or test or reference) near (pattern or portion))) and ((calculat\$5 or determin\$4) with (bias\$4 or deviat\$4))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/11/18 21:12
52	14	((electron adj beam) and lithograph\$3) and (edge near2 width)) and ((calculat\$5 or determin\$4) with (dimension\$4))) and ((second or test or reference) near (pattern or portion))) and ((calculat\$5 or determin\$4) with (bias\$4 or deviat\$4))) and focus\$4	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/11/18 21:12

53	3	(((((electron adj beam) and lithograph\$3) and (edge near2 width)) and ((calculat\$5 or determin\$4) with (dimension\$4))) and ((second or test or reference) near (pattern or portion))) and ((calculat\$5 or determin\$4) with (bias\$4 or deviat\$4))) and focus\$4) and (exposure near2 energ\$4)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/11/18 21:12
54	3	(((((electron adj beam) and lithograph\$3) and (edge near2 width)) and ((calculat\$5 or determin\$4) with (dimension\$4))) and ((second or test or reference) near (pattern or portion))) and ((calculat\$5 or determin\$4) with (bias\$4 or deviat\$4))) and focus\$4) and ((exposure or dos\$4) near2 energ\$4)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/11/18 21:13
55	2	(((((electron adj beam) and lithograph\$3) and (edge near2 width)) and ((calculat\$5 or determin\$4) with (dimension\$4))) and ((second or test or reference) near (pattern or portion))) and ((calculat\$5 or determin\$4) with (bias\$4 or deviat\$4))) and focus\$4) and ((exposure or dos\$4) near2 energ\$4)) and correct\$4	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/11/18 21:14
56	43036	imag\$5 with electron	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/11/18 21:14
57	5735	(imag\$5 with electron) and (resist or photoresist)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/11/18 21:15
58	4907	((imag\$5 with electron) and (resist or photoresist)) and pattern\$4	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/11/18 21:15
59	87	((imag\$5 with electron) and (resist or photoresist)) and pattern\$4) and ((calculat\$5 or determin\$4) near5 ((characteristic or critical) near2 dimension\$3))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/11/18 21:17
60	74	((imag\$5 with electron) and (resist or photoresist)) and pattern\$4) and ((calculat\$5 or determin\$4) near5 ((characteristic or critical) near2 dimension\$3))) and width and edge	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/11/18 21:17
61	39	((imag\$5 with electron) and (resist or photoresist)) and pattern\$4) and ((calculat\$5 or determin\$4) near5 ((characteristic or critical) near2 dimension\$3))) and width and edge) and ((second or test or reference) near (pattern or portion))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/11/18 21:18
62	9	((imag\$5 with electron) and (resist or photoresist)) and pattern\$4) and ((calculat\$5 or determin\$4) near5 ((characteristic or critical) near2 dimension\$3))) and width and edge) and ((second or test or reference) near (pattern or portion))) and ((calculat\$5 or determin\$5) with (change or deviation or bias\$4) with exposure)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/11/18 21:20

64	4	(((((((imag\$5 with electron) and (resist or photoresist)) and pattern\$4) and ((calculat\$5 or determin\$4) near5 ((characteristic or critical) near2 dimension\$3))) and width and edge) and ((second or test or reference) near (pattern or portion))) and ((calculat\$5 or determin\$5) with (change or deviation or bias\$4) with exposure)) and (correct\$4 with exposure)) and model\$4	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/11/18 21:21
63	6	(((((((imag\$5 with electron) and (resist or photoresist)) and pattern\$4) and ((calculat\$5 or determin\$4) near5 ((characteristic or critical) near2 dimension\$3))) and width and edge) and ((second or test or reference) near (pattern or portion))) and ((calculat\$5 or determin\$5) with (change or deviation or bias\$4) with exposure)) and (correct\$4 with exposure)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/11/18 21:21

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1	12065	imag\$5 near2 electron	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/11/18 22:17
2	2908	((imag\$5 near2 electron) and (resist or photoresist or mask or photomask))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/11/18 22:18
3	165	((imag\$5 near2 electron) and (resist or photoresist or mask or photomask)) and ((characteristic or critical) near dimension\$4)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/11/18 22:19
4	106	((((imag\$5 near2 electron) and (resist or photoresist or mask or photomask)) and ((characteristic or critical) near dimension\$4)) and (edge and width or (edge-width)))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/11/18 22:20
5	34	(((((imag\$5 near2 electron) and (resist or photoresist or mask or photomask)) and ((characteristic or critical) near dimension\$4)) and (edge and width or (edge-width))) and (second near2 (pattern or portion or area)))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/11/18 22:35
6	16	((((((imag\$5 near2 electron) and (resist or photoresist or mask or photomask)) and ((characteristic or critical) near dimension\$4)) and (edge and width or (edge-width))) and (second near2 (pattern or portion or area))) and ((calculat\$5 or determin\$5) with (deviat\$4 or bias\$4)))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/11/18 22:24
7	16	((((((imag\$5 near2 electron) and (resist or photoresist or mask or photomask)) and ((characteristic or critical) near dimension\$4)) and (edge and width or (edge-width))) and (second near2 (pattern or portion or area))) and ((calculat\$5 or determin\$5) with (deviat\$4 or bias\$4))) and energ\$4	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/11/18 22:25
8	2	((((((imag\$5 near2 electron) and (resist or photoresist or mask or photomask)) and ((characteristic or critical) near dimension\$4)) and (edge and width or (edge-width))) and (second near2 (pattern or portion or area))) and ((calculat\$5 or determin\$5) with (deviat\$4 or bias\$4))) and energ\$4 and (correct\$4 with (exposure or energ\$4 or dos\$4))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/11/18 22:26
9	15	((((((imag\$5 near2 electron) and (resist or photoresist or mask or photomask)) and ((characteristic or critical) near dimension\$4)) and (edge and width or (edge-width))) and (second near2 (pattern or portion or area))) and ((calculat\$5 or determin\$5) with (deviat\$4 or bias\$4))) and energ\$4 and (correct\$4 and (exposure or dos\$4))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/11/18 22:26
10	15	((((((imag\$5 near2 electron) and (resist or photoresist or mask or photomask)) and ((characteristic or critical) near dimension\$4)) and (edge and width or (edge-width))) and (second near2 (pattern or portion or area))) and ((calculat\$5 or determin\$5) with (deviat\$4 or bias\$4))) and energ\$4 and (correct\$4 and (exposure or dos\$4))) and (model\$4 or reference or librar\$4 or simulat\$5)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/11/18 22:27

11	15	(((((imag\$5 near2 electron) and (resist or photoresist or mask or photomask)) and ((characteristic or critical) near dimension\$4)) and (edge and width or (edge-width))) and (second near2 (pattern or portion or area))) and ((calculat\$5 or determin\$5) with (deviat\$4 or bias\$4)) and energ\$4) and (correct\$4 and (exposure or dos\$4))) and (model\$4 or reference or librar\$4 or simulat\$5)) and focus\$4	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/11/18 22:32
12	3	(((((imag\$5 near2 electron) and (resist or photoresist or mask or photomask)) and ((characteristic or critical) near dimension\$4)) and (edge and width or (edge-width))) and (second near2 (pattern or portion or area))) and ((calculat\$5 or determin\$5) with (deviat\$4 or bias\$4)) and energ\$4) and (correct\$4 and (exposure or dos\$4))) and (model\$4 or reference or librar\$4 or simulat\$5)) and focus\$4) and (plus or minus or sign)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/11/18 22:30
13	2	(((((imag\$5 near2 electron) and (resist or photoresist or mask or photomask)) and ((characteristic or critical) near dimension\$4)) and (edge and width or (edge-width))) and (second near2 (pattern or portion or area))) and ((calculat\$5 or determin\$5) with (deviat\$4 or bias\$4)) and energ\$4) and (correct\$4 and (exposure or dos\$4))) and (model\$4 or reference or librar\$4 or simulat\$5)) and focus\$4) and (calculat\$4 with (deviat\$4 or bias\$4) with focus)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/11/18 22:36
14	360	(calculat\$4 with (dimension\$3 near (characteristic or critical)))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/11/18 22:35
15	49	((calculat\$4 with (dimension\$3 near (characteristic or critical))) and (second near (pattern or portion or area)))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/11/18 22:36
16	4	((calculat\$4 with (dimension\$3 near (characteristic or critical))) and (second near (pattern or portion or area))) and ((calculat\$4 or determin\$5) with (deviat\$4 or bias\$4) with focus)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/11/18 22:39
17	4	((calculat\$4 with (dimension\$3 near (characteristic or critical))) and (second near (pattern or portion or area))) and ((calculat\$4 or determin\$5) with (deviat\$4 or bias\$4) with focus)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/11/18 22:43
18	3160	((calculat\$4 or determin\$5) with (change or deviat\$4 or bias\$4) with exposure)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/11/18 22:55
19	1191	((calculat\$4) with (change or deviat\$4 or bias\$4) with exposure)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/11/18 22:55
20	1260	((calculat\$4 or determin\$5) with (change or deviat\$4 or bias\$4) with exposure)) and ((correct\$4 or compensat\$5) with exposure)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/11/18 22:56

21	1087	(((((calculat\$4 or determin\$5) with (change or deviat\$4 or bias\$4) with exposure)) and ((correct\$4 or compensat\$5) with exposure)) and (model\$4 or reference))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/11/18 22:56
22	214	(((((calculat\$4 or determin\$5) with (change or deviat\$4 or bias\$4) with exposure)) and ((correct\$4 or compensat\$5) with exposure)) and (model\$4	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/11/18 22:57
23	250	(((((calculat\$4 or determin\$5) with (change or deviat\$4 or bias\$4) with exposure)) and ((correct\$4 or compensat\$5) with exposure)) and (model\$4 or reference)) and ((second or test or reference) near (pattern or portion))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/11/18 22:58
24	20	(((((calculat\$4 or determin\$5) with (change or deviat\$4 or bias\$4) with exposure)) and ((correct\$4 or compensat\$5) with exposure)) and (model\$4 or reference)) and ((second or test or reference) near (pattern or portion)) and (calculat\$5 near4 dimension\$3)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/11/18 22:59
25	16	(((((calculat\$4 or determin\$5) with (change or deviat\$4 or bias\$4) with exposure)) and ((correct\$4 or compensat\$5) with exposure)) and (model\$4 or reference)) and ((second or test or reference) near (pattern or portion)) and (calculat\$5 near4 dimension\$3)) and electron	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/11/18 22:59
26	16	(((((calculat\$4 or determin\$5) with (change or deviat\$4 or bias\$4) with exposure)) and ((correct\$4 or compensat\$5) with exposure)) and (model\$4 or reference)) and ((second or test or reference) near (pattern or portion)) and (calculat\$5 near4 dimension\$3)) and electron) and pattern	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/11/18 22:59
27	14	(((((calculat\$4 or determin\$5) with (change or deviat\$4 or bias\$4) with exposure)) and ((correct\$4 or compensat\$5) with exposure)) and (model\$4 or reference)) and ((second or test or reference) near (pattern or portion)) and (calculat\$5 near4 dimension\$3)) and electron) and pattern) and width	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/11/18 23:00
28	5	(((((calculat\$4 or determin\$5) with (change or deviat\$4 or bias\$4) with exposure)) and ((correct\$4 or compensat\$5) with exposure)) and (model\$4 or reference)) and ((second or test or reference) near (pattern or portion)) and (calculat\$5 near4 dimension\$3)) and electron) and pattern) and width) and (electron near5 imag\$5)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/11/18 23:03
29	5	(((((calculat\$4 or determin\$5) with (change or deviat\$4 or bias\$4) with exposure)) and ((correct\$4 or compensat\$5) with exposure)) and (model\$4 or reference)) and ((second or test or reference) near (pattern or portion)) and (calculat\$5 near4 dimension\$3)) and electron) and pattern) and width) and (electron near5 imag\$5)) and (resist or photoresist)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/11/18 23:03

30	3	(((((((((calculat\$4 or determin\$5) with (change or deviat\$4 or bias\$4) with exposure)) and ((correct\$4 or compensat\$5) with exposure)) and (model\$4 or reference)) and ((second or test or reference) near (pattern or portion))) and (calculat\$5 near4 dimension\$3)) and electron) and pattern) and width) and (electron near5 imag\$5)) and (resist or photoresist)) and monitor\$5	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/11/18 23:05
31	5	(((((((((calculat\$4 or determin\$5) with (change or deviat\$4 or bias\$4) with exposure)) and ((correct\$4 or compensat\$5) with exposure)) and (model\$4 or reference)) and ((second or test or reference) near (pattern or portion))) and (calculat\$5 near4 dimension\$3)) and electron) and pattern) and width) and (electron near5 imag\$5)) and (resist or photoresist)) and process	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/11/18 23:08
32	3	(((((((((calculat\$4 or determin\$5) with (change or deviat\$4 or bias\$4) with exposure)) and ((correct\$4 or compensat\$5) with exposure)) and (model\$4 or reference)) and ((second or test or reference) near (pattern or portion))) and (calculat\$5 near4 dimension\$3)) and electron) and pattern) and width) and (electron near5 imag\$5)) and (resist or photoresist)) and observ\$6	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/11/18 23:06
34	4	(((((((((calculat\$4 or determin\$5) with (change or deviat\$4 or bias\$4) with exposure)) and ((correct\$4 or compensat\$5) with exposure)) and (model\$4 or reference)) and ((second or test or reference) near (pattern or portion))) and (calculat\$5 near4 dimension\$3)) and electron) and pattern) and width) and (electron near5 imag\$5)) and (resist or photoresist)) and process) and ((characteristic or critical\$3) near dimension\$4)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/11/18 23:09
33	5	(((((((((calculat\$4 or determin\$5) with (change or deviat\$4 or bias\$4) with exposure)) and ((correct\$4 or compensat\$5) with exposure)) and (model\$4 or reference)) and ((second or test or reference) near (pattern or portion))) and (calculat\$5 near4 dimension\$3)) and electron) and pattern) and width) and (electron near5 imag\$5)) and (resist or photoresist)) and process) and ((characteristic or critical\$3)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/11/18 23:26